Press Release
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Nanonex
Engine for Nanotechnology ™

Nanonex delivered NX 2600 to Wright-Patterson Laboratory, Ohio.

Princeton NJ, July. 01, 2010:

Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of a Nanonex NX-2600 to Wright-Patterson Laboratory, OH. Nanonex is proud to support the leading edge research at the Wright-Patterson Lab.

The Nanonex NX-2600 is a full wafer nanoimprinter and photolithography aligner. It is capable of all imprint forms: thermal, photo-curable, embossing and photolithography, with sub-5nm imprinting resolution and sub-1 micrometer alignment accuracy. Based on the Nanonex unique patented Air Cushion Press™ technology, the NX-2600 offers unsurpassed uniformity regardless of backside topology, wafer or mask flatness, or backside contamination. This ACP technology also eliminates lateral shifting between the mask and substrate, which significantly increases mask lifetime.

The NX-2600 tool was purchased by The Air Force Research Laboratory, Sensors Directorate. The NX-2600 will be used as a tool for nanomanufacturing and nano/micro fabrication at Wright Patterson Air Force Base in the cutting edge research of infrared sensing, biotronics, photonics, and meta-materials.